## **Complexes Containing Cobalt-Silicon Metal-Metal Bonds**

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*Summary* The complexes  $(Ph_3P)_3COH_2(SiR_3)$   $(R = F,$ OEt) are formed by an oxidative-elimination reaction between  $R_s$ SiH and  $(Ph_sP)_sCo(N_s)H$ ; the reaction is reversible when  $R = OEt$ , and this complex functions as an efficient catalyst for O-silylation and hydrosilylation reactions.

THE only known silyl complexes of the first-row transition metals involve low oxidation states of the metals, which are stabilized by carbonyl or cyclopentadienyl ligands.<sup>1</sup> There appear to be no silyl complexes of these metals which contain only tertiary phosphines as the neutral ligand, nor are there any in which the metal is in a high formal oxidation state.<sup>†</sup>

We now report the first complexes of this type, the cobalt(III) complexes  $(Ph_3P)_3CoH_2(SiR_3)$  (I;  $R = F$ , OEt), obtained as yellow solids by the oxidative-elimination reaction of the silane  $R_3$ SiH with the dinitrogen complex **(II),<sup>2</sup>** suspended in hexane. Reaction proceeds smoothly at room temperature with loss of one molar equivalent of nitrogen. Similar preparative routes have been used to

$$
\begin{array}{c}(\mathrm{Ph_3P})_3\mathrm{Co(N_2)H}\,+\,\mathrm{R_3SiH}\rightarrow (\mathrm{Ph_3P})_3\mathrm{CoH_2(SiR_3)}\,+\, \mathrm{N_2}\\(\mathrm{II})\qquad \qquad (\mathrm{I})\end{array}
$$

make silyl derivatives of the heavier metals.<sup>3</sup> Under similar conditions no reaction occurs when  $R = Et$ , and when  $R = Cl$  chlorination of cobalt occurs to give the known<sup>4</sup> complex  $(Ph<sub>3</sub>P)<sub>3</sub>CoCl (III).$ 

The silyl complexes  $(I; R = F$  or OEt) decompose rapidly in air, but are stable *in vacuo* or under argon. Under nitrogen, however,  $(I; R = OEt)$  loses the R<sub>3</sub>SiH and reforms (II).  $(I; R = F)$  is stable to dissociation in benzene-hexane, from which solvent it may be recrystallised; (I;  $R = OEt$ ) dissociates in this solvent system.



 $(I; R = OEt)$  can also be obtained by the reaction of the cobalt compound  $(Ph_3P)_3CoH_3$  (IV)<sup>4</sup> with the silane in an atmosphere of argon. This reaction is related to that **of**  (IV) with nitrogen to give **(11),5** and all three complexes can be interconverted reversibly:  $(I; R = F)$  can be prepared from (IV), but is unaffected by nitrogen or hydrogen.

In addition to bands characteristic of  $Ph<sub>3</sub>P$  and  $-SiR<sub>3</sub>$ , the i.r. spectra of (I) show weak absorptions at *ca.* 1945 cm<sup>-1</sup> which are probably due to Co-H stretching vibrations. The **100** MHz lH n.m.r. spectra (benzene) show single, broad (ca. 40 Hz halfwidth) signals at  $\tau$  24.9 (R = F) and 25.1

t **Cyclopentadienyl derivatives of some of these metals in high formal oxidation states have been reported since the submission of this communication** (W. **Jetz and W. A. G. Graham,** *Inorg.* **Chem., 1971,10, 4).** 

 $(R = OEt)$ , which compare with a resolved quartet  $(J_{P-H})$ *ca.*  $50 \text{ Hz}$ ) at  $\tau$  29 for (II).<sup>6</sup> The lack of fine structure for the silyl complexes suggests a rapid exchange process, although no dissociation was detected in a molecular weight determination on  $(I; R = F)$  in the same solvent. compare with a resolved quartet  $(f_{P-H}^{--})$ <br>for (II).<sup>6</sup> The lack of fine structure for<br>s suggests a rapid exchange process,<br>tion was detected in a molecular weight<br> $\langle I, R = F \rangle$  in the same solvent.<br> $\langle I, R = F \rangle$  in the same

The complexes  $(I; R = F, OEt)$  react with carbon tetrachloride to give the silane R<sub>3</sub>SiH, chloroform, and (III); as previously reported, $^{5}$  (III) reacts further with carbon tetrachloride to form  $(Ph_3P)_2CoCl_2$ .

 $(I; R = OEt)$  and its precursors  $(II)$  and  $(IV)$  are useful homogeneous catalysts for O-silylation and for hydrosilylation reactions, *e.g.* reactions **(1)** and **(2).** Reaction **(1)** 

$$
\text{SiH(OEt)}_{3} \xrightarrow{\text{catalyst}} \xrightarrow{\text{EtOH} \rightarrow \text{Si(OEt)}_{4} + \text{H}_{2}} \qquad (1)
$$
\n
$$
\text{hex-1-ene} \rightarrow \text{n-C}_{\text{a}H_{11} \text{Si(OEt)}_{3}} \qquad (2)
$$

proceeds *via* (IV), since the rapid occurrence of reaction **(3)** 

$$
(\text{Ph}_3\text{P})_3\text{CoH}_2\text{Si}(\text{OEt})_3 + \text{EtOH} \rightarrow (\text{Ph}_3\text{P})_3\text{CoH}_3 + \text{Si}(\text{OEt})_4 \tag{3}
$$

probably has been demonstrated independently. The complex (IV) then reacts with triethoxysilane to regenerate (I; R = OEt). Reaction **(1)** is quite rapid, being *80%*  complete in  $2.5 h$  with a  $2: 1: 2 \times 10^{-4}$  molar ratio of ethanol : silane : catalyst. O-Silylation has recently been shown to be similarly catalysed by dicobalt octacarbonyl.'

Reaction **(2)** is very vigorous and strongly exothermic. With  $2:1:2\times10^{-4}$  and  $1:1:2\times10^{-4}$  molar ratios of hex-l-ene : silane : catalyst the temperature of the mixture rises from *25* "C to *Ga.* **65** "C in **4** min and the reaction is **75%** and **40%** complete, respectively, in 10min. If the mixture is deliberately kept at  $25-30$  °C  $(2:1:2\times10^{-4}$ ratio), *ca.*  $40\%$  reaction occurs in 20 min. In all cases, some isomerisation of the olefin also occurs; at  $25-30$  °C the rate of isomerisation is about half that of hydrosilylation. Unlike the cobalt carbonyl catalysed hydrosilylation reaction,6 it seems probable that reaction **(2)** proceeds *via* a silyl-complex, presumably  $(I; R = OEt)$ . The more stable complex  $(I; R = F)$  does not react with hex-1-ene, and attempts to catalyse the reaction of this olefin with trifluorosilane, using (11), resulted only in the formation of  $(I; R = F).$ 

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